

RECEIVED
CENTRAL FAX CENTERPATENT APPLICATION
Docket No.: NC 84,613

AUG 29 2005

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the application of: Walton et al.

Serial No.: 10/644,567

Filed: 08/20/2003

For: ELECTRON BEAM ENHANCED LARGE AREA DEPOSITION SYSTEM

Examiner: McDonald, Rodney Glenn

Art Group Unit: 1753

Honorable Commissioner of Patents

PO Box 1450

Alexandria, VA 22313-1450

August 29, 2005

RESPONSE TO FINAL REJECTION

Sir:

In response to the Office action of 05/27/2005, setting a three month shortened statutory period of reply, please consider the following remarks.

A Notice of Appeal is attached.

Claims 1-10 and 12-21 are pending in the application. Claims 16-21 are withdrawn subject to a restriction requirement. No claims are presently allowed.

Interview Summary

The Examiner, Inventor Scott Walton, and Applicants' representative conducted an in-person interview on 07/12/2005. It was discussed whether there was a motivation to combine the Meger reference with the Moseson reference. The Examiner agreed that there was no such motivation because Meger required high energy electron beams and Moseson teaches away from using high energy electron beams, and because Meger lacks a teaching that the apparatus may be used for deposition. The fact that there was no motivation was documented in the Examiner's Interview Summary, however, during the interview he stated that this finding was subject to

CERTIFICATE OF FACSIMILE TRANSMISSION

I certify that this correspondence is being facsimile transmitted to the US Patent and Trademark Office on the date shown below.

8/29/05
Date


Joseph T. Grunkemeyer